

Amendments to the Claims:

Following is a complete listing of the claims pending in the application, as amended:

1. (Currently amended) A stepper or scanner machine for processing microfeature workpieces, the machine comprising:
 - a housing;
 - an illuminator disposed within the housing;
 - a lens disposed within the housing;
 - a workpiece support disposed within the housing;
 - a cleaning device, a cleaning fluid supply having a liquid-phase cleaning fluid, and a vacuum pump all disposed within the housing to remove contaminants from the workpiece support, the cleaning device being operably coupled to the vacuum pump ~~and~~, in fluid communication with the cleaning fluid supply, and configured to deliver the liquid-phase cleaning fluid to the workpiece support; and
 - a stage carrying the workpiece support, at least one of the stage and the cleaning device being movable relative to the other to selectively position the workpiece support at least proximate to the cleaning device.
2. (Original) The machine of claim 1 wherein the cleaning device comprises an end effector configured to engage the workpiece support to remove contaminants.
3. (Original) The machine of claim 1, further comprising a positioning device coupled to the cleaning device to move the cleaning device relative to the housing.
4. (Currently amended) A stepper or scanner machine for processing microfeature workpieces, the machine comprising:
 - a housing;
 - an illuminator disposed within the housing;
 - a lens disposed within the housing;
 - a workpiece support disposed within the housing;

a cleaning fluid supply having a liquid-phase cleaning fluid;

a cleaning device in fluid communication with the cleaning fluid supply and disposed
within the housing to remove contaminants from the workpiece support; and
a stage carrying the workpiece support, at least one of the stage and the cleaning device
being movable relative to the other to selectively position the workpiece support
at least proximate to the cleaning device;

wherein the cleaning device is fixed relative to the housing.

5. (Previously presented) The machine of claim 1 wherein the vacuum pump is configured to draw the contaminants from the workpiece support.

6. (Currently amended) The machine of claim 1, further comprising a cleaning fluid supply;

wherein the cleaning device comprises a first passageway in fluid communication with the cleaning fluid supply to provide ~~a~~ the liquid-phase cleaning fluid to the workpiece support and a second passageway to exhaust the liquid phase cleaning fluid from the workpiece support.

7. (Original) The machine of claim 1, wherein:
the workpiece support comprises a recess to receive a microfeature workpiece; and
the cleaning device comprises a distal portion positionable at least partially in the recess to remove contaminants from the recess.

8. (Original) The machine of claim 1, further comprising a controller operably coupled to the stage and having a computer-readable medium containing instructions to perform a method comprising positioning the workpiece support under the cleaning device.

9. (Original) The machine of claim 1, further comprising a controller operably coupled to the cleaning device and having a computer-readable medium containing instructions to perform a method comprising moving the cleaning device relative to the housing.

10. (Original) The machine of claim 1, further comprising a controller operably coupled to the stage and the cleaning device, the controller having a computer-readable medium containing instructions to perform a method comprising moving the cleaning device and the stage to position the cleaning device at least proximate to the workpiece support.

11. (Currently amended) A stepper or scanner machine for processing microfeature workpieces, the machine comprising:

a photolithographic exposure system;

a workpiece support having a recess to receive a microfeature workpiece, the workpiece support being positionable at least proximate to the photolithographic exposure system;

a cleaning fluid supply having a liquid-phase cleaning fluid;

an internal cleaning device having a distal portion with a first passageway in fluid communication with the cleaning fluid supply to provide ~~a~~ the liquid-phase cleaning fluid to the workpiece support and a second passageway to exhaust the liquid-phase cleaning fluid from the workpiece support; and

a stage carrying the workpiece support, at least one of the stage and the cleaning device being movable relative to the other to position the distal portion of the cleaning device at least proximate to the recess of the workpiece support.

12. (Original) The machine of claim 11, further comprising a housing enclosing the internal cleaning device, the workpiece support, and the stage.

13. (Original) The machine of claim 11 wherein the distal portion of the cleaning device comprises an end effector configured to engage the workpiece support.

14. (Original) The machine of claim 11, further comprising:

a housing enclosing the workpiece support, the stage, and the internal cleaning device;
and

a positioning device coupled to the cleaning device to move the cleaning device relative to the housing.

15. (Currently amended) A stepper or scanner machine for processing microfeature workpieces, the machine comprising:

a photolithographic exposure system;

a workpiece support having a recess to receive a microfeature workpiece, the workpiece support being positionable at least proximate to the photolithographic exposure system;

a cleaning fluid supply having a liquid-phase cleaning fluid;

an internal cleaning device in fluid communication with the cleaning fluid supply and having a distal portion with a passageway for removing contaminants from the recess of the workpiece support;

a stage carrying the workpiece support, at least one of the stage and the cleaning device being movable relative to the other to position the distal portion of the cleaning device at least proximate to the recess of the workpiece support; and

a housing enclosing the workpiece support, the stage, and the internal cleaning device, wherein the cleaning device is fixed relative to the housing.

16. (Previously presented) The machine of claim 11, further comprising a vacuum pump operably coupled to the second passageway of the cleaning device to draw contaminants from the recess of the workpiece support and a housing enclosing the internal cleaning device, the workpiece support, the vacuum pump, and the stage.

17. (Previously presented) The machine of claim 11 wherein the first and second passageways are in a generally concentric arrangement.

18. (Currently amended) A stepper or scanner machine for processing microfeature workpieces, the machine comprising:

a housing;

a photolithographic system disposed within the housing for patterning a layer of resist on a microfeature workpiece;

a workpiece support within the housing, the workpiece support having a recess to receive the microfeature workpiece;

a cleaning fluid supply having a liquid-phase cleaning fluid;

a means for removing contaminants from the recess of the ~~microfeature-workpiece support~~, the means for removing contaminants being in fluid communication with the cleaning fluid supply and disposed within the housing; and

a stage carrying the workpiece support, the stage being movable relative to the means for removing contaminants to selectively position the workpiece support at least proximate to the means for removing contaminants.

19. (Original) The machine of claim 18 wherein the means for removing contaminants comprises an end effector configured to engage the workpiece support to remove contaminants.

20. (Original) The machine of claim 18 wherein:

the means for removing contaminants comprises a distal portion with a passageway; and

the machine further comprises a vacuum pump operably coupled to the passageway to draw contaminants from the workpiece support.

21. (Currently amended) The machine of claim 18, further comprising a cleaning fluid supply;

wherein the means for removing contaminants comprises a first passageway in fluid communication with the cleaning fluid supply to provide ~~a~~ the liquid-phase cleaning fluid to the workpiece support and a second passageway to exhaust the liquid-phase cleaning fluid from the workpiece support.

22-55. (Cancelled)

56. (Previously presented) The machine of claim 11 wherein the first and second passageways are in a generally concentric arrangement with the first passageway surrounding the second passageway.